

Application number

1541084

Registration number

TMA872980

Type(s)

Word

Category

Trademark

CIPO Status

REGISTERED

TM5 status

LIVE/REGISTRATION/Issued and Active



The trademark application has been registered with the Office.

Filed

2011-08-25

Registered

2014-03-10

Registration Expiry Date

2029-03-10

Registered Owner

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Agent

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Documents

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Index headings

PICOSUN
PICO SUN

Goods (Nice class & Statement)

(1) Machines and machine tools for atomic scale layer deposition; atomic scale layer deposition apparatus, namely, reactors, reactor systems consisting of several reactors, precursor sources, inactive gas sources, plasma sources, source systems, loading systems, lift systems, substrate holders, deposition cartridges, diffusion enhancers, gas treatment systems, particle traps, water cooling systems and chillers, all of which can be sold as an integral part of the atomic scale layer deposition reactors or reactor systems consisting of several reactors or as a separate accessories thereto; Data processing equipment, namely computers, computer memories, viewing screens and touch screens, keyboards, computer pointing devices, central processing units (CPU's), printers and scanners; computer programmes for controlling and monitoring atomic scale layer deposition apparatus, namely reactors and reactor systems consisting of several reactors, for collecting data from aforementioned atomic scale layer deposition apparatus, user interface software for use in atomic layer deposition (ALD), computer software for use in atomic layer deposition (ALD) enabling interface and communication with reactors, reactor systems consisting of several reactors, precursor sources, inactive gas sources, plasma sources, source systems, loading systems, lift systems, substrate holders, deposition cartridges, diffusion enhancers, gas treatment systems, particle traps, water cooling systems and chillers, computer software for controlling and monitoring reactors, reactor systems consisting of several reactors, precursor sources, inactive gas sources, plasma sources, source systems, loading systems, lift systems, substrate holders, deposition cartridges, diffusion enhancers, gas treatment systems, particle traps, water cooling systems and chillers used in atomic layer deposition (ALD).

Services (Nice class & Statement)

Classification data

Disclaimer

The classification data is provided for information and searching purposes only. CIPO does not warrant the accuracy of the classes assigned to the trademark. This data has no legal value of any kind.

Claims

Used in CANADA since at least as early as May 2006
Priority Filing Date: August 16, 2011,
Country or

(1) Treatment and coating of materials by atomic scale layer deposition method and consulting connected thereto.

- 7 - Machinery
- 9 - Electrical, scientific and teaching apparatus and software
- 11 - Environmental control items
- 40 - Treatment of materials

Office: FINLAND, Application No. T201102432 in association with the same kind of goods and in association with the same kind of services
Used in FINLAND

Registered in or for FINLAND on December 15, 2011, under No. 253819

Action History

Action	Action date	Due date	Comments
Filed	2011-08-25		
Created	2011-08-25		
Formalized	2011-08-31		
Search Recorded	2012-02-28		
Examiner's First Report	2012-02-28	2012-08-28	
Correspondence Created	2012-11-13	2013-05-13	
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Approved	2013-07-04		APPROVED BY PROGRAM EX200M1
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Allowed	2013-11-08		
Allowance Notice Sent	2013-11-08	2014-05-08	
Rep for Service Changed	2014-02-17		From: 6166 To: 16080 / Voir Preuve au dossier /See evidence on File No. 1541084
Agent Changed	2014-02-17		From: 6166 To: 16080 / Voir Preuve au dossier /See evidence on File No. 1541084
Registered	2014-03-10	2029-03-10	